

Notice of References Cited	Application/Control No. 09/853,345	Applicant(s)/Patent Under Reexamination FONTANA ET AL.	
	Examiner John A. McPherson	Art Unit 1756	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
	A	US-			
	B	US-			
	C	US-			
	D	US-			
	E	US-			
	F	US-			
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FOREIGN PATENT DOCUMENTS

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NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	"Chemistry of Ketal Resist System and its Lithographic Performance", Huang et al., pages 95-109 of Micro-and Nanopatterning Polymers, American Chemical Society, 9/1997.
	V	
	W	
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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